

Abstract Submitted  
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**Magnetotransport of Epitaxial Graphene on Hexagonal SiC Surface Grown with Metal Plate Capping**<sup>1</sup> KIBOG PARK, HAN BYUL JIN, SUNGCHUL JUNG, JUNHYOUNG KIM, Ulsan Natl Inst of Sci Tech, DONGHUN CHAE, WAN-SEOP KIM, JAESUNG PARK, Korea Research Institute of Standards and Science — High quality epitaxial graphene (EG) was grown on a Si-face hexagonal SiC substrate by capping the surface with a metal plate (Molybdenum, Tungsten) during UHV annealing. The growth temperature was  $\sim 950$  degree C, significantly lower than the conventional UHV annealing. The crystallinity of EG film was examined with Raman spectrum measurements. Almost no D-peak and a large narrow 2D-peak ensure that a thin (mono- or bi-layer) EG film was grown with a negligible number of defects. The electrical properties of EG film were also characterized by performing magnetotransport measurements with Hall-bar structures. The carrier type was found to be n-type, the sheet carrier density be  $(3.6-9.2) \times 10^{12} / \text{cm}^2$ , and the Hall mobility be  $\sim 2100 \text{ cm}^2/\text{Vs}$ . Due to the relatively high carrier density, the Quantum Hall Effect was observed only for high filling factors up to 14 T. However, clear Shubnikov-de-Hass oscillations were observed, indicating that the random carrier scattering due to impurities or defects is minimal in the EG film grown with metal plate capping.

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